i.

+703-905-2500

T-262 P.001 F-033

Intellectual FROM Property Group of Pillsbury Winthrop LLP

Attorneys at Law P.O. Box 10500 McLean, VA 22102

RECEIVED CENTRAL FAX CENTER

Telephone: (703) 905-2000

Our Facsimile #: (703) 905-2500

APR 2 9 2004

FACSIMILE TRANSMISSION

AFFIAIA

		UDW ARETOR		UFFICIAL
TO: <u>UNITED S</u>	TATES PATENT AND TRADEM	ARK_OFFICE		
FACSIMILE #:	(703) <u>872-9306</u>			
No. Pages (In	cluding this page) 8	FAX Op	r: <u>Tnera:</u>	a Togba
IF YOU DO NOT	RECEIVE CLEARLY ALL PA	GES, PLEASE CONTACT	US IMMEDIATEL	<u> </u>
	By Telephone AT: (703)	905-2205 : (703) 905-2000(loc	(local)	
->->->	<u>USPTO:</u> PLEASE <u>ACKNOWLEDG</u> ABOVE BY FAXING T NUMBERS STATED AB	E CLEAR RECEIPT OF HIS PAGE BACK TO ON NOVE	ALL PAGES INDIC E OF OUR FACSI	CATED VILE
In re PAT	ENT APPLICATION of			
Inventor(E) INABA 10/042,264	-	o Arc Unit: iner:	2826 , Thomas L.
	code † † serial no.			
Filed:	January 11, 2002	Atty	. Dkt. <u>PM 0</u> 2	284163 M#
TITLE:	SEMICONDUCTOR DE METHOD OF FABRIC SAME		: April 29,	
REQUEST F	ype of <u>signed</u> paper bei <u>OR RECONSIDERATION TRAN</u> E:	<u>SMITTAL; REQUEST FO</u>	R RECONSIDERATI	ON
				•
Forms Directo	Sec.; Transmit only <u>onc</u> paper ory PAT-286 Rear Do <u>not</u> fil nd fax receipt on top. Do <u>vo</u>	e originals but fasten t	DOM TU GAL LITE (1	ert gide) with
	CERTI	FICATE OF FACSIMILE	TRANSMISSION	
and Tradem	I hereby certify that ark Office on the date	this paper is being shown below.	racsimile tras	ismitted to the Patent
	n P. Darling Sig	1100	line Date A	pril 29, 2004
	No. 44482	44020/0284163	7	
		C# / M#		

PAT-286 7/99

Attorney's Docket 044020-0284163

Client Reference: 01F181

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 6258

INABA

Application No.: 10/042,264

Group Art Unit: 2826

Filed: January 11, 2002

Examiner: Dickey, Thomas L.

For: SEMICONDUCTOR DEVICE AND METHOD OF FABRICATING THE SAME

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

REQUEST FOR RECONSIDERATION TRANSMITTAL

Transmitted herewith is an amendment/response for this application.

FEES

The fee for claims and extension of time (37 C.F.R. 1.16 and 1.17) has been calculated as shown below:

***************************************	CLAIMS REMAINING AFTER AMENDMENT	PRE	IEST NO. VIOUSLY ID FOR		ESENT	RA	TE		ADDIT	
TOTAL	46	_	46	=	0	x s	18.00	=	s	0.00
, , , , , , ,			<u>.=</u>			x				
INDEP.	10	_	10	=	0	\$	86.00	=	\$	0.00
FIRST PRESENTATION OF MULTIPLE DEP. +										
CLAIM						\$	290.00	=	\$	0.00
TOTAL ADDITIONAL CLAIM FEE GRAND TOTAL							AIM FEE		\$	0.00
								\$	0.00	

INABA - - 10/042,264

Client/Matter: 044020-0284163

FEE PAYMENT

Authorization is hereby made to charge the amount of \$0.00 to Deposit Account No. 033975. Charge any additional fees required by this paper or credit any overpayment in the manner authorized above. A duplicate of this paper is attached.

Date: April 29, 2004

PILLSBURY WINTHROP LLP

P O. Box 10500 McLean, VA 22102 (703) 905-2000 Customer No.: 00909 Red. No. 44482

Tel. No.: (703) 905-2045 Fax No.: (703) 905-2500

Attorney's Docket 044020-0284163 Client Reference: 01F181



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 6258

INABA

Application No.: 10/042,264

Group Art Unit: 2826

Filed: January 11, 2002

Examiner: Dickey, Thomas L.

For: SEMICONDUCTOR DEVICE AND METHOD OF FABRICATING THE SAME

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

REQUEST FOR RECONSIDERATION TRANSMITTAL

Transmitted herewith is an amendment/response for this application.

FEES

The fee for claims and extension of time (37 C.F.R. 1.16 and 1.17) has been calculated as shown below:

	CLAIMS REMAINING AFTER AMENDMENT	PRE\	EST NO. /IOUSLY D FOR		ESENT (TRA	RA	TE		ADDIT.	
TOTAL	46	_	46	=	0	× \$	18.00	=	\$	0.00
INDEP.			· 10		0	×	86.00	=	\$	0.00
FIRST PRESENTATION OF MULTIPLE DEP. +								=		0.00
CLAIM				TAL .	A DDITIO	NAL CL			•	0.00
TOTAL ADDITIONAL CLAIM FEE GRAND TOTAL								\$ \$	0.00	

INABA - - 10/042,264

Client/Matter: 044020-0284163

FEE PAYMENT

Authorization is hereby made to charge the amount of \$0.00 to Deposit Account No. 033975. Charge any additional fees required by this paper or credit any overpayment in the manner authorized above. A duplicate of this paper is attached.

Date: April 29, 2004

PILLSBURY WINTHROP LLP

P.O. Box 10500 McLean, VA 22102 (703) 905-2000

Customer No.: 00909

JOHN P. DARLING

Reg. No. 44482

Tel. No.: (703) 905-2045 Fax No.: (703) 905-2500

RECEIVED
CENTRAL FAX CENTER

APR 2 9 2004

Attorney Docket: 044020-0284163

Client Reference: 01F181

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

OFFICIAL

In re PATENT APPLICATION of:

Confirmation Number: 6258

INABA

Application No.: 10/042,264

Group Art Unit: 2826

Filed: January 11, 2002

Examiner: Dickey, Thomas L.

Title: SEMICONDUCTOR DEVICE AND METHOD OF FABRICATING THE SAME

REQUEST FOR RECONSIDERATION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In reply to the Office Action dated January 29, 2004, reconsideration in view of the following remarks is respectfully requested.

Claims 1, 4-6 and 11 were rejected under 35 U.S.C. §102(b) over Yazawa et al. (U.S. Patent 4,819,043). The rejection is respectfully traversed.

Claim 1 recites a semiconductor device comprising, *inter alia*, a first impurity doped layer equal to or less in junction depth than the extension region of each of a source/drain diffusion layer. The pair of source and drain diffusion layers are formed in the semiconductor substrate to oppose each other with a channel region laterally residing therebetween at a location immediately beneath a gate electrode. Yazawa et al. do not disclose or suggest these features.

Yazawa et al. disclose a MOSFET with reduced short channel effect, otherwise known as a "buried channel device." In such a device, a channel is formed deep inside the substrate, not immediately beneath the gate electrode. In the device of Yazawa et al., a channel is formed in an N-type layer 6 (in the ON state of the MOSFET only), not in the P-type layer 7. (See column 2, lines 20-34 and the cross hatched region of Figure 3b). The N-type layer 6 is sandwiched between the P-type layer 7 and a P-type substrate 1. A gate electrode 3 is formed over the P-type layer 7 via insulating film 2. Accordingly, Yazawa et

INABA -10/042,264

Client/Matter: 044020-0284163

al. do not disclose or suggest a channel formed immediately beneath the gate electrode as recited in claim 1, lines 6-7.

The Office Action on page 3, line 1, alleges that Yazawa et al. disclose a channel region 6-7. However, the P-type layer 7 of Yazawa et al. is not a channel region. The P-type layer 7 of Yazawa et al. is not a channel region as it is of opposite conductivity type to the source/drain layers 4 or 5 and no "diffusion layer" is formed therein, even in the ON state of the MOSFET. (See Figures 3b and 6e.)

The Office Action on page 3, lines 9-8, also alleges that N-type layer 6 of Yazawa et al. is a second impurity layer as recited in claim 1. However, it is respectfully submitted that the N-type layer 6 of Yazawa et al. is not a second impurity layer as recited in claim 1. The N-type layer 6 of Yazawa et al. is depleted only in the OFF state of the MOSFET. In the ON state, the depletion layer is contracted and a channel is formed in the N-type layer 6. Thus, the N-type layer 6 does not provide characteristics similar to that of a fully depleted SOI MOSFET.

Finally, in the device of Yazawa et al., the source and drain diffusion layers 4 and 5 have an extension region. However, the extension regions in Yazawa et al. extend toward the P-type layer 7, in which no channel is formed, and not toward the N-type layer 6, in which the channel is formed.

For the above reasons, it is respectfully submitted that Yazawa et al. do not anticipate claim 1.

Claims 2-11 recite additional features of the invention and are allowable for the same reasons discussed above with respect to claim 1, and for the additional features recited therein.

Reconsideration and withdrawal of the rejection of claims 1-11 are respectfully requested.

In view of the above remarks, Applicants respectfully submit that all the claims are allowable and that the entire application is in condition for allowance.

INABA - 10/042,264

2004-04-29 15:21

Client/Matter: 044020-0284163

Should the Examiner believe that anything further is desirable to place the application in better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number listed below.

Respectfully submitted,

PILLSBURY WINTHROP LLP

Reg. No. 44482

Tel. No. (703) 905-2045 Fax No. (703) 905-2500

Date: April 29, 2004

P.O. Box 10500 McLean, VA 22102 (703) 905-2000

Customer No.: 00909